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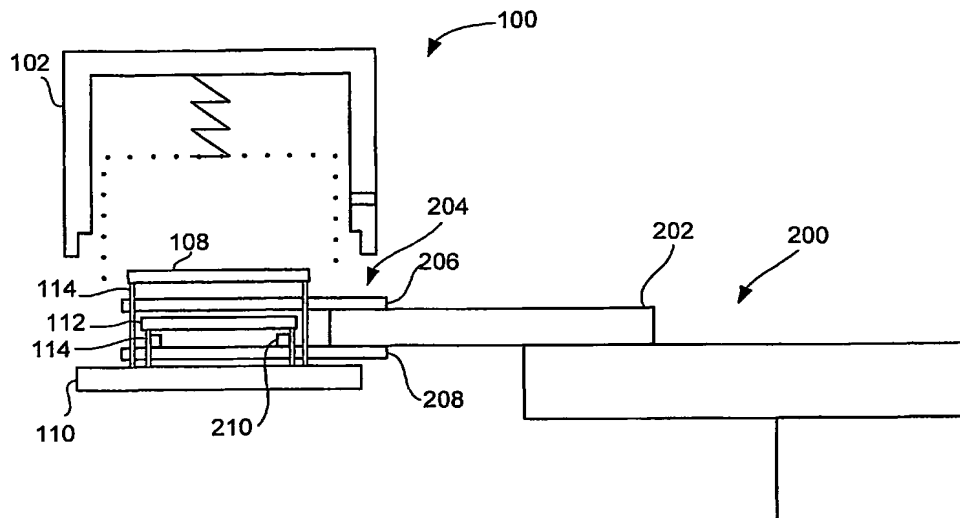
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(54) Title: THERMOPHORETIC TECHNIQUES FOR PROTECTING RETICLES FROM CONTAMINANTS



(57) Abstract: Thermophoresis within lithography systems for protecting reticles from contaminants (e.g., floating particles). Generally, thermophoretic protection is implemented by maintaining the reticle at a higher temperature than its surrounding environment. Thermophoretic protection can be maintained throughout a reticle's use in a lithography system. For example, a reticle can be thermophoretically protected while in storage, through various stages of transportation via a reticle handler (also referred to as an end-effector), to its period of use while attached to a reticle chuck.



SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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